MOCVD Reactors

Taiyo Nippon Sanso Corporation (TNSC) was the first in the world to develop MOCVD equipment to produce compound semiconductors utilized in LEDs, lasers, and high performance electronics for applications such as mobile phones, advanced lighting, and optical communications systems.







UR Series Reactors for Mass Production

GaN and related alloy processing for wafer diameters up to 200 mm

SR Series Reactors for Research and Small Scale Production

GaN and related alloy processing with integrated low vapor pressure source delivery capability for novel alloys (e.g., Al_xSc_{1-x}N) for wafer diameters up to 150 mm

FR Series Reactors for Research and Small Scale Production

 Ga_2O_3 and related alloy processing for wafers up to 100 mm

BRC/BMC Series Reactors for Research and Mass Production

GaAs, InP, and related alloy processing for wafer diameters up to 150 mm

TNSC, along with its sister companies, MATHESON (U.S.) and Nippon Gases (Europe), offers complete end-to-end solutions for MOCVD customers:

- Arsine (AsH₃), Phosphine (PH₃), Silane (SiH₄), and Ammonia (NH₃) and other primary gases that are used in MOCVD applications.
- Ultrapurification equipment for integration with MOCVD equipment for highest quality processing.
- Gas handling equipment and abatement solutions for safe and reliable MOCVD operations.

Contact us for more information at info@tnsc-innovation.com.



